

QUANTUM DEVICES WITH 2D SEMICONDUCTORS AND INSULATORS

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In this talk I will describe two applications of 2D layered materials for quantum devices. First, I will discuss our work to fabricate and characterize gate-defined, accumulation mode quantum dots using monolayer and bilayer WSe2 (Figure 1) [1]. The devices are operated with gates above and below the WSe2 layer to accumulate a hole gas, which for some devices is then selectively depleted to define the dot. Temperature dependence of conductance in the Coulomb-blockade regime is consistent with transport through a single level, and excited-state transport through the dots is observed at temperatures up to 10 K. These devices provide a platform to evaluate valley-spin states in monolayer and bilayer WSe₂ for application as qubits. Second, I will discuss gate-tunable Josephson junction field-effect transistors (JJ-FETs) based on Al/InAs in which the gate dielectric is thin hBN [2]. Comparing devices with hBN and AlOx dielectrics, we observe that the product of normal resistance and critical current, IcRn, is comparable for both types of devices, but strikingly higher Rn for the hBN-based devices indicating that the surface is doped less compared to AlOx gate dielectric. These results demonstrate that h-BN provides a superior gate dielectric compared to AlO_x for JJ-FET devices with applications in superconducting logic and quantum information technologies such as gatemon qubits and topological superconductivity.



Gate voltage Figure 1. Coulomb diamond with resolved excited states for a gate-defined bilayer WSe₂ quantum dot.

References

[1] S. Davari, *et al.* Phys. Rev. Appl. 13, 054058 (2020).
[2] W. Mayer, *et al.* arXiv:2007.12202.